

We are excited to introduce the BEAM Engine Gen 2 - a generational leap forward from Gen 1, delivering new levels of precision, speed, and reliability for advanced lithography applications. The Gen 2 will be standard on new systems at no additional cost and available as an upgrade for Gen 1 users.

Next-generation performance: Outpaces previous models with higher resolution, faster exposures, and enhanced process flexibility.

Advanced patterning capabilities: Native greyscale and seamless stitching expand the range of achievable micro- and nano-structures, supporting cutting-edge device fabrication.

Operational efficiency: Lower maintenance needs translate to more uptime and lower total cost of ownership.

Interchangeable lens design

- Achieve resolutions down to 0.5 μm
- Supports high-throughput patterning at speeds up to 200 mm^2/min

Accelerated exposures

- Single writefield exposures as fast as 250 ms.

Native 256-level greyscale support

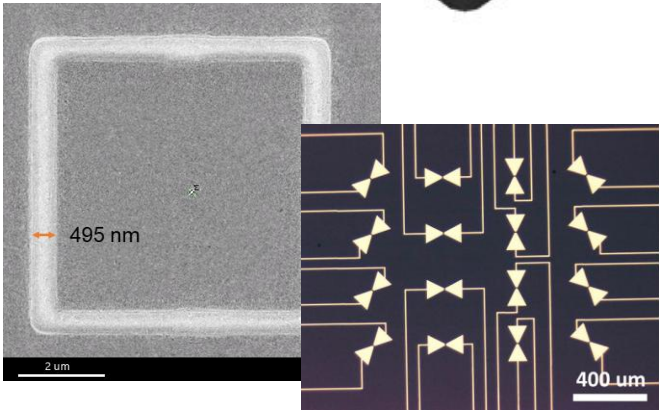
- True 8-bit greyscale lithography for advanced 2.5D and 3D microstructure fabrication

Seamless stitching

- Gradient stitch with up to 100% overlap

Low maintenance

- Solid-state architecture reduces moving parts and wear
- 80% reduction in required calibrations, minimizing downtime and maintenance costs



SPECIFICATIONS

	50x	20x	10x	5x
Minimum Linewidth (um)	0.5	0.8	1.5	3
Patterning speed (mm ² /min)	3	15	60	200
Exposure Wavelength (nm)	405 (standard), 365 and 385 (option)			
Greyscale	256 Levels (8-bits)			